

Art Unit: 2800

CLMPTO

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EG

1. Method of manufacturing a diffusing reflector comprising the processes of:

preparing for a substrate;

forming a resin film having photosensitivity on said substrate;

providing gathering of pillar-shaped bodies isolated each other through patterning of said resin film with the photolithography;

forming uneven surface layer having the maximum inclination angle of under 12° by gently deforming individual said pillar-shaped bodies through the reflow; and

forming a metal film on gathering of said gently deformed uneven surface layer.

2. Method of manufacturing a diffusing reflector as claimed in claim 1, wherein said maximum inclination angle is about 10° .

3. Method of manufacturing a diffusing reflector as claimed in claim 1, comprising a process of alleviating said maximum inclination angle by coating said gently deformed uneven surface layer with resin to bury the flat opening between said uneven surface layers isolated each other.

4. Method of manufacturing a diffusing reflector as claimed in claim 1, wherein said reflow process is the heat treatment under the temperature of about 220°C.

5. Method of manufacturing a diffusing reflector as claimed in claim 1, wherein gathering of polygonal pillar-shaped bodies isolated each other by the divided patterning of said resin film by said photolithography is provided.

6. Method of manufacturing a diffusing reflector as claimed in claim 5, wherein said resin film is patterned by the divided patterning means so that size of gap between said polygonal pillar-shaped bodies isolated each other is almost equal to the minimum resolution of photolithography.